

# SiC vs IGBT Costs & SiC Substrate Surface Quality

Llew Vaughan-Edmunds

Director of Strategic and Technical Marketing

PowerAmerica Panel Discussion | Aug 3-5, 2021

# ICAPS

IoT

Coms

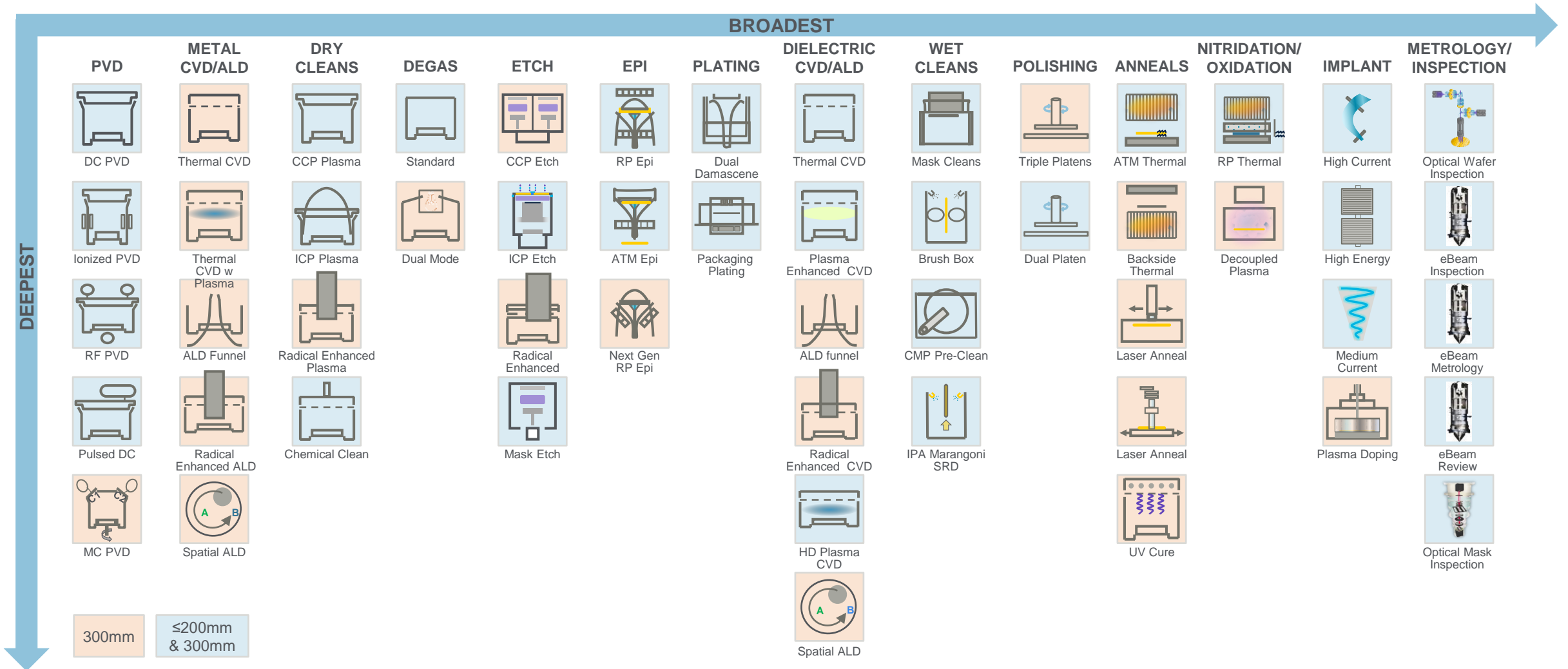
Auto

Power

Sensor

Increase focus on specialty markets  
Better serve diverse customer base  
Pursue opportunities for new technology and new business models

# ICAPS | Applied Materials Product Portfolio



**150 / 200 / 300mm Wafer Fab Equipment for Silicon and Compound Semiconductors**

# Agenda

1

IGBT vs SiC MOSFET cost –  
transitioning to larger wafer sizes

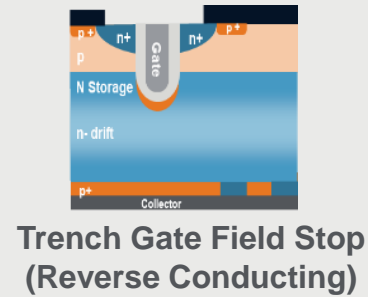
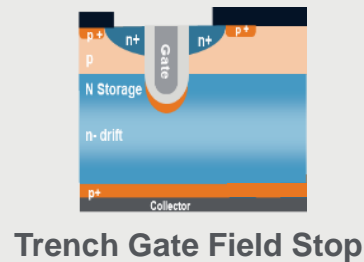
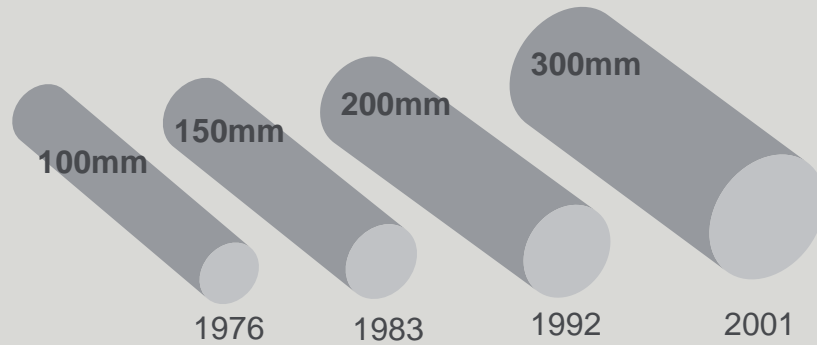
2

SiC substrate surface quality –  
ready for epitaxial growth

# 200mm Silicon Wafers - In Production for 30 Years

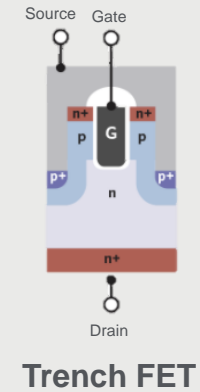
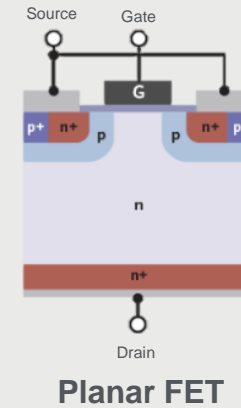
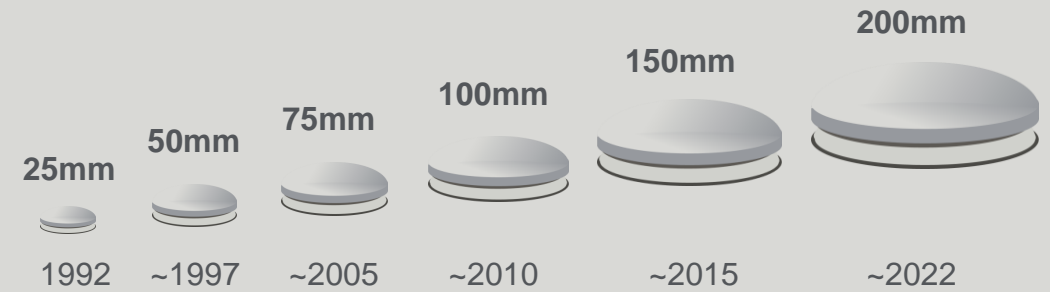
## 200mm Silicon Carbide Wafers - Start Production in 2022

### IGBT



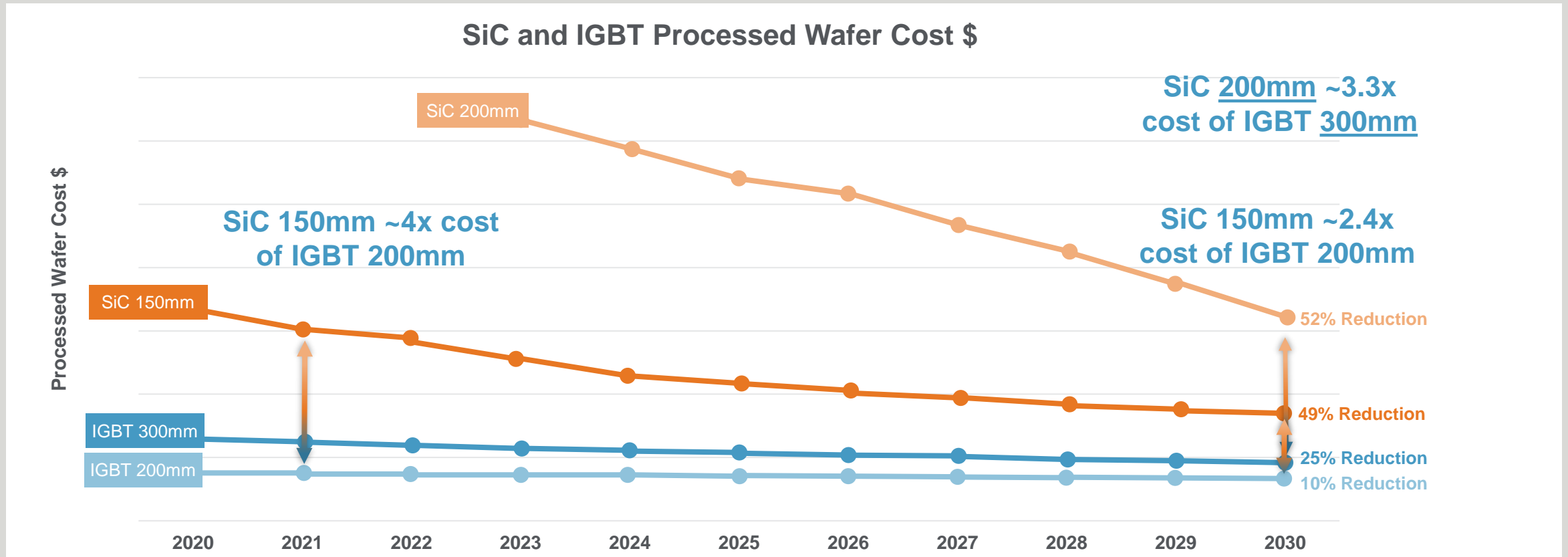
### SiC MOSFET

\*High volume production



# Processed Wafer Cost of SiC MOSFET Will Always Cost More Than Si IGBT

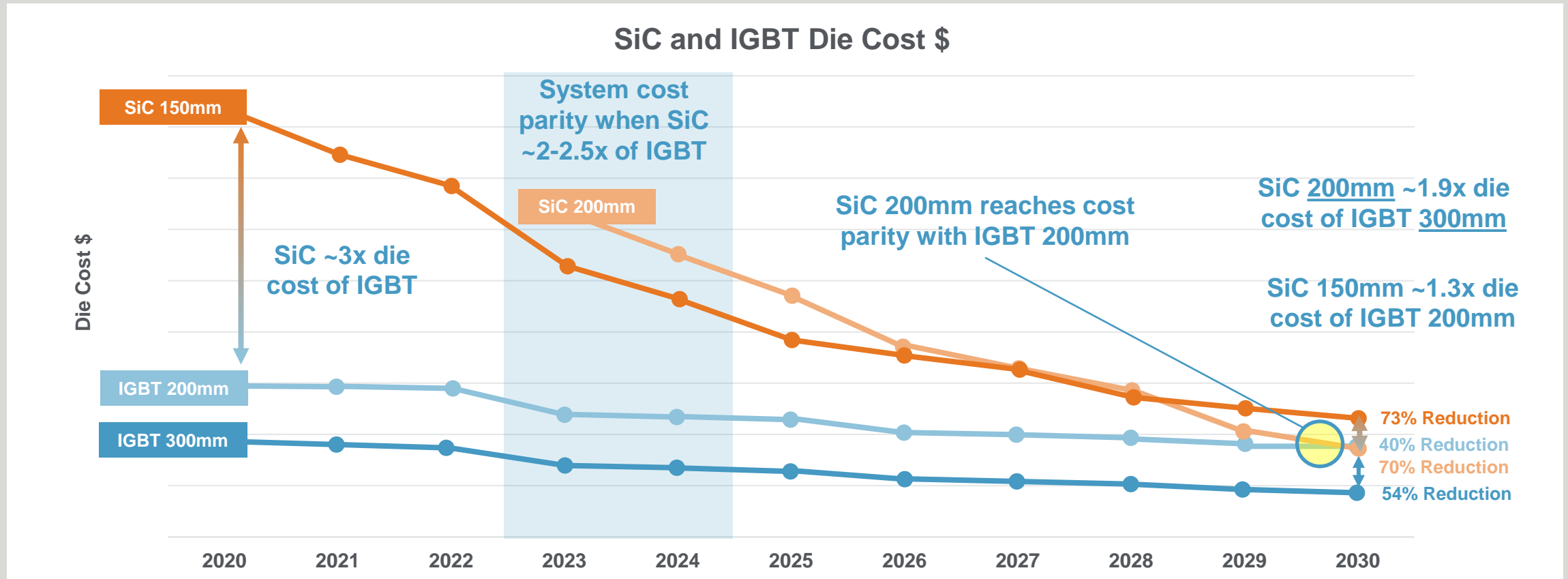
- SiC Processed Wafer Cost will Decrease ~50% by 2030



Source: Systems Plus, Omdia, PowerQ Consulting, Applied Materials

# SiC MOSFETs Must Transition to 200mm Wafers to Compete with IGBTs at 300mm

- SiC die cost parity in 2029; however IGBTs will transition to 300mm



Source: Systems Plus, PowerQ Consulting, Applied Materials

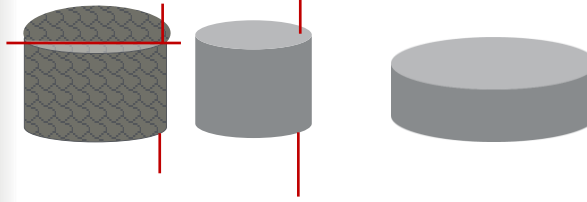
# Creating a Finished SiC Substrate

## Sawing, Grinding and Polishing Second-Hardest Material in World!

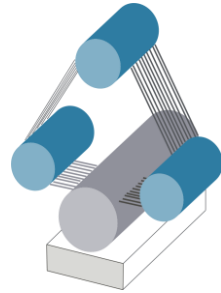
Raw Boule



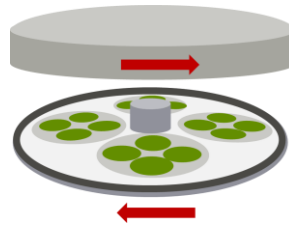
Processed Boule



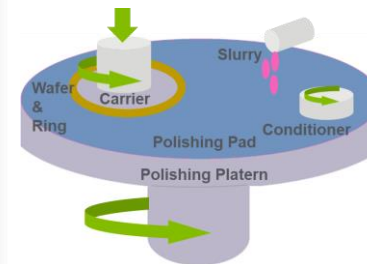
Slice – Wire Saw Laser



Mechanical Processing  
(Grind and Lapping)



Chemical Mechanical  
Polish (CMP) and Etch



Finished Substrate



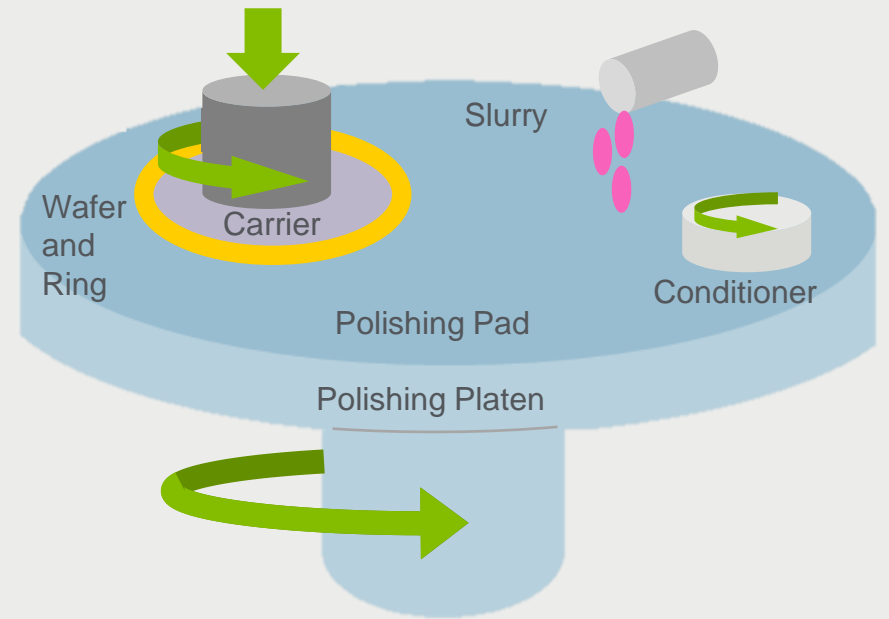
Image Source: Entegris



# Highest-Quality Surface Critical for Epitaxial Growth with Fewest Defects



- Flat
- Smooth
- No Scratches
- No Particles
- No Pits



# CMP Requirements to Enable High Volume Manufacturing

## Highest Quality

- Single-wafer processing (vs. batch)
  - ▶ Wafer-to-wafer repeatability/performance
- Insensitivity to pre-CMP wafer thickness variations
- Ability to modulate within-wafer thickness (multi-zone polishing head)
- Optimization in polishing sequence using multi-slurry configurations

## Highest Productivity

- High throughput
  - ▶ Dry in, dry out
  - ▶ Wafer cleaning, drying
  - ▶ Material weight removal measurement
  - ▶ Wafer ID reading
- Lowest cost of ownership
  - ▶ Cost of slurries, pads, other consumables, power, cooling/cleaning water, etc.
- Capable of 200mm wafers

# Summary

1. SiC MOSFET processed wafers will always cost more than Silicon IGBT processed wafers. However, **SiC die cost will reduce to ~1.3x of IGBT in 2030** (150mm SiC vs 200mm IGBT)
2. **SiC substrate surfaces must be of the highest quality** to support the best epitaxial growth, resulting in fewer defects, and **higher device yield and reliability**
3. To meet the **surging demand** in EV, manufacturing tools, including CMP, must be **superior in manufacturing quality, throughput, and competitiveness**



APPLIED  
MATERIALS®

make possible